

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of: **INOUE, et al.**

Group Art Unit: 2823

Serial No.: 09/228,148

Examiner: **MALDONADO, Julio J.**

Filed: **January 11, 1999**

P.T.O. Confirmation No.: 7239

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FOR: SEMICONDUCTOR DEVICE INCLUDING AN INSULATION FILM ON A CONDUCTIVE LAYER AND MANUFACTURING METHOD THEREOF

REQUEST FOR RECONSIDERATION

Commissioner for Patents
Washington, D.C. 20231

November 12, 2002

Sir:

In response to the Office Action dated **August 12, 2002**, Applicants request favorable reconsideration of the above-identified application. Claims 9-18 are pending.

Claims 9, 10, 13 and 15-18 were rejected under 35 U.S.C. §103(a) as being unpatentable over Leong in view of Sasaki et al. This rejection is respectfully traversed.

The Examiner acknowledges that Leong fails to teach an intrusion prevention film to substantially prevent the impurities introduced into the first insulation film from entering the conductive layer. The Examiner relies upon the teachings of Sasaki et al for allegedly rendering such an intrusion prevention film obvious "since the silicon oxide prevents contamination due to diffusion of impurities into layers below that of the oxide."

Sasaki et al would fail to motivate one of ordinary skill in the art to make the modifications of Leong as asserted by the Examiner. Although Sasaki et al teaches a contamination prevention film, this film is provided on an insulating substrate 30 for preventing contamination due to diffusion of impurities such as alkaline metals (see column 10, lines 44-49). Sasaki et al fails to suggest to one of ordinary skill in the art to employ an intrusion prevention film to substantially prevent the impurities introduced into said first insulation film from entering said conductive layer as set forth in claim 9. In other words, Sasaki et al would not have provided any suggestion to have modified Leong to provide an intrusion prevention film as asserted by the Examiner.

Even if one of ordinary skill in the art would have combined the references, it would appear that the combination would not lead to the present invention. At most, Sasaki et al teaches providing a contamination prevention film on the substrate of Leong. Such a combination would not prevent impurities introduced into said first insulation film from entering said conductive layer.

Claim 14 was rejected under 35 U.S.C. §103(a) as being unpatentable over Leong in view of Sasaki et al and further in view of Wolf. This rejection is respectfully traversed.

Wolf is applied by the Examiner for allegedly rendering obvious a first insulation film including silicon oxide containing at least one percent carbon. Wolf fails to provide the teachings which Leong and Sasaki et al lack, as discussed above.

Applicants acknowledge the indication that claims 11 and 12 would be allowable if rewritten in independent form. However, for the reasons discussed above, it is respectfully submitted that all presently pending claims are in condition for allowance.

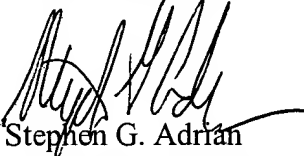
An Information Disclosure Statement is filed herewith updating related copending applications and references cited therein. The Examiner is requested to acknowledge consideration of the Information Disclosure Statement in the next communication.

For at least the foregoing reasons, the claimed invention distinguishes over the cited art and defines patentable subject matter. Favorable reconsideration is earnestly solicited.

Should the Examiner deem that any further action by applicants would be desirable to place the application in condition for allowance, the Examiner is encouraged to telephone applicants' undersigned attorney.

Respectfully submitted,

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Attachment: Information Disclosure Statement